



CyberOptics® Shares Best Practice Process Insights for Reticle Environments at SPIE Photomask Technology 2014

Panel session will feature CyberOptics spokesperson discussing how best to improve processes in reticle mask environments

Monterey, CA —September 15, 2014— [CyberOptics Corporation](#) (NASDAQ: CYBE), a world leader in intelligent inspection and sensing solutions for electronics assembly and semiconductor process equipment, will present at the upcoming [SPIE Photomask Technology 2014](#), the premier worldwide technical meeting for the photomask industry, at the Monterey Marriott Hotel and Convention Center, September 16-18, 2014.

A [panel session](#) on Tuesday, September 16 at 4:35 p.m. will feature Allyn Jackson, Field Application Engineer for CyberOptics, discussing: “Improving Efficiency and Effectiveness of Processes Related to Airborne Particle Measurement in Reticle Mask Environments.”

“Minimizing airborne particles in photomask applications remains critical in semiconductor processes. Quickly identifying when and where airborne particles originate and the source of the contamination is challenging with traditional surface scan reticle, in-situ or hand-held methods. However, using a wireless, wafer-like and real-time particle counter results in compelling advantages in terms of time, expense and productivity,” said Allyn Jackson, Field Application Engineer.

Whether for equipment diagnostics, particle qualification or preventative maintenance, equipment engineers need to identify and troubleshoot airborne particle issues efficiently and effectively. Legacy methods are not real time, may cause long delays for results and are costly with downtime required to tear down the fab tool or run a series of test reticles. Without real-time-feedback, often ‘unexpected’ particle sources can also go undetected or take a long time to finally identify. Legacy methods can also lead to delays in equipment qualification, equipment release to production and maintenance cycles.

Lithography engineers can rely on CyberOptics ReticleSense proprietary technology, which is an extension of the proven WaferSense® wafer-shaped Airborne Particle Sensor (APS) device in use at semiconductor fabs worldwide including the three largest manufacturers where a contamination-free environment is critical.

For more information about the entire line of CyberOptics solutions please visit the company’s website at www.cyberoptics.com.

About CyberOptics

Founded in 1984, CyberOptics Corporation is a leading provider of sensors and inspection systems that provide process yield and through-put improvement solutions for the global electronic assembly and semiconductor capital equipment markets. Our products are deployed on production lines that manufacture surface mount technology circuit boards and semiconductor process equipment. Through

internal development and acquisitions, CyberOptics is strategically repositioning itself to become a global leader in high-precision 3D sensors. Headquartered in Minneapolis, Minnesota, CyberOptics conducts worldwide operations through facilities in North America, Asia and Europe.

Statements regarding the Company's anticipated performance are forward-looking and therefore involve risks and uncertainties, including but not limited to: market conditions in the global SMT and semiconductor capital equipment industries; increasing price competition and price pressure on our product sales, particularly our SMT systems; the level of orders from our OEM customers; the availability of parts required for meeting customer orders; unanticipated product development challenges; the effect of world events on our sales, the majority of which are from foreign customers; product introductions and pricing by our competitors; the level of revenue and loss we record in 2014; the success of our 3D technology initiatives; expectations regarding LDI and its impact on our operations; integration risks associated with LDI and other factors set forth in the Company's filings with the Securities and Exchange Commission.

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